

U.S. Application #

Pat.	App. Num.	Publ'd Num.	Status	Date Filed	Inventor Name	Title
	06071551		1B1	05/05/2005	DAVIS, TODD	Anticorrosional polymer coating
	06212184		1B1	09/21/2001	DAVIS, TODD	Anticorrosional wetting instruments
	05981913		1B1	09/18/2001	DAVIS, TODD	Anti-hijacking cockpit door system for aircraft
	10563904		030	09/17/2003	DAVIS, TODD	Adaptive lithographic critical dimension enhancement
	10582416		030	10/10/2003	DAVIS, TODD	Methods to improve resolution of cross sectioned features created using an ion beam
	10717813		082	11/21/2003	DAVIS, TODD	METHOD FOR DEVELOPING A PHOTOREGIST PATTERN
	10731430		030	12/10/2003	DAVIS, TODD	Integrated lithographic fabrication cluster

Docket: HEN-VD - (2132204 01:55:34)

TOC: 10563904 - VD, HEN (2563) - ADAPTIVE LI

Information Disclosure Statement 112




Applications for inventor: DAVIS, TODD

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U.S. Application #

Pat.	App. Num.	Pub. # Num.	Status	Date Filed	Inventor Name	Title
1	11/542501		051	06/17/2003	PAXTON, THEODORE	Amplitude-dependent cross-sectional dimension enhancement
2	11/542716		052	10/02/2003	PAXTON, THEODORE	Methods to improve resolution of cross-sectioned features created using an ion beam
3	11/547175-1		053	11/21/2003	PAXTON, THEODORE	METHOD FOR DEVELOPING A PHOTORESIST PATTERN
4	11/5721410		050	12/02/2003	PAXTON, THEODORE	Integrated lithographic fabrication cluster
5	11/5783088		070	09/23/2004	PAXTON, THEODORE	Wafer processing apparatus and method of use

U.S. Application #

Pat.	App. Num.	Publ. Num.	Status	Date Filed	Inventor Name	Title
	10042941		63d	04/17/2003	HAR, TODD	Adaptive ultrasonic critical dimension measurement
	13711433		03c	12/10/2003	HAR, TODD	Integrated lithographic fabrication device
	15763956		07d	03/23/2004	HAR, TODD	Wafer processing apparatus and method of use

DocId: 10042941-12132004 07:10:45

DOC-10042941-v2, HEN (1553) - ADAPTIVE U.

Applications for Inventor: HAR, TODD

U.S. Application #

Pat.	App. Num.	Publ'd Num.	Status	Date Filed	Inventor(s)	Title
5	100521007		257	06/14/2003	TEL, YIM	METHOD OF ADAPTED PROGRAMMABLE LOGIC APPARATUS FOR SELECTING AND MAINTAINING ACTIONS BY A COORDINATE PROCESSING SYSTEM
5	100540046		041	06/17/2003	TEL, YIM	Adaptive thermal control of lithographic chemical processes
5	100613804		030	06/17/2003	TEL, YIM	Adaptive lithographic optical dimension enhancement
5	100780001		070	07/08/2004	TEL, YIM	Lithographic projection apparatus and a device manufacturing method using such lithographic projection apparatus
5	100980005		070	07/08/2004	TEL, YIM	Modification of an image of a pattern during an imaging process
5	100980087		070	07/08/2004	TEL, YIM	Lithographic exposure and device manufacturing method

Docket: HEN VO - (2132004 071045)

TOC: 10063904 - VO; HEN Q883 - ADAPTIVE U.

Applications for Invention: TEL, YIM

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U.S. Application #

Pat.	App. Num.	Publ'd Num.	Status	Date Filed	Inventor Name	Title
	9502181		181	05/07/2001	DAVIS, TODD	Antireflectal polymer coating
	09/12184		181	09/12/2001	DAVIS, TODD	Antireflectal wiring structures
	09/25593		181	09/18/2001	DAVIS, TODD	Anti-jacking cockpit door system for aircraft
	10/063004		030	09/17/2003	DAVIS, TODD	Adaptive lithographic critical dimension enhancement
	10/087444		030	10/10/2003	DAVIS, TODD	Methods to improve resolution of cross sectioned features created using an ion beam
	10/917813		082	11/21/2003	DAVIS, TODD	METHOD FOR DEVELOPING A PHOTORESIST PATTERN
	10/731430		030	12/10/2003	DAVIS, TODD	Integrated lithographic fabrication process

	Type	L#	Hits	Search Text	DBs	Time Stamp	Comments	Error Definition	Er
1	IS&R	L1	6	(("5229872") or ("5296891") or ("5523193") or ("5969441") or ("6046792") or ("20020081758")).PN	US-P GPUB:06:21 USPA T	2004/12/13			
2	BRS	L2	0	1 and substrate and attribut\$3 and exposure and lithograph\$3	US-P GPUB:06:22 USPA T	2004/12/13			
3	BRS	L3	0	1 and substrate and attribut\$3 and expos\$3 and lithograph\$3	US-P GPUB:06:22 USPA T	2004/12/13			
4	BRS	L4	0	1 and substrate and attribut\$3 and expos\$3	US-P GPUB:06:23 USPA T	2004/12/13			
5	BRS	L5	26	substrate and attribut\$3 and expos\$3 and lithograph\$3 and uniform and regulat\$3 and dosage	US-P GPUB:06:24 USPA T	2004/12/13			

	U	Document ID	Issue Date	Pages	Title	Current OR	Current XR	Retrieval C	Inventor	S	C	P	3	
1		US 5510628 A	19960423	20	Deep ultraviolet photolithographically defined ultra-thin films for selective cell adhesion and outgrowth and method of manufacturing the same and devices containing the same	257/32	257/37; 257/E21.174; 257/E21.175; 430/315; 435/29; 438/1		Georger, Jr.; Jacque H. et al.			P	P	P
2		US 5324591 A	19940628	21	Deep ultraviolet photolithographically defined ultra-thin films for selective cell adhesion and outgrowth and method of manufacturing the same and devices containing the same	428/552	257/E21.174; 257/E21.175; 428/336; 430/296; 438/1		Georger, Jr.; Jacque H. et al.			P	P	P
3		US 5079600 A	19920107	17	High resolution patterning on solid substrates	257/750	257/629; 257/E21.174; 257/E21.175; 427/553; 427/558; 427/97.4; 430/314; 430/315; 438/669; 438/694		Schnur, Joel M. et al.			P	P	P
4		US 20040171038 A1	20040902	102	IL-1 gene cluster and associated inflammatory polymorphisms and haplotypes	435/6			Nicklin, Martin et al.			P	P	P
5		US 20040142974 A1	20040722		4,4-disubstituted piperidines, and methods of use thereof	514/326	514/317; 546/207; 546/236		Hoemann, Michael Z.			P	P	P
6		US 20040077090 A1	20040422		Whole cell engineering by mutagenizing a substantial portion of a starting genome, combining mutations, and optionally repeating	435/471	435/252.3; 435/254.2		Short, Jay M.			P	P	P
7		US 20040067512 A1	20040408		Single nucleotide polymorphisms and mutations on Alpha-2-Macroglobulin	435/6			Becker, Kenneth David et al.			P	P	P
8		US	20040219		Polymorphisms of PD-1	435/6	536/23.2		Alarcon-Riquelme,					

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16	US 20020169562 A1	20021114	63	Defining biological states and related genes, proteins and patterns	702/19	435/6; 530/350; 536/23.1	Stephanopoulos, Gregory et al.
17	US 20020156092 A1	20021024	41	Diazabicyclo[4.3.0]nonanes, and methods of use thereof	514/300	546/113	Wu, Xinhe
18	US 20020127144 A1	20020912	38	Device for analyzing particles and method of use	422/81	422/82.01; 422/82.05; 422/82.08; 422/82.09; 436/149; 436/150; 436/164; 436/172	Mehta, Shailesh P.
19	US 20020034757 A1	20020321	140	Single-molecule selection methods and compositions therefrom	435/6	435/91.2; 536/22.1; 536/23.1; 536/24.3	Cubiccioni, Roger S.
20	US 6762025 B2	20040713	129	Single-molecule selection methods and compositions therefrom	435/6	435/91.2; 536/22.1; 536/23.1; 536/24.3; 536/24.5	Cubiccioni, Roger S.
21	US 6656953 B2	20031202	40	4,4-Disubstituted piperidines, and methods of use thereof	514/317		Hoemann, Michael Z.
22	US 6476046 B1	20021105	37	Diazabicyclo[4.3.0]nonanes, and methods of use thereof	514/300	514/292; 546/113; 546/84	Wu, Xinhe

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	U	Document ID	Issue Date	Pages	Title	Current OR	Current XR	Retrieval C	Inventor	S	C	P	1
1	<input type="checkbox"/>	US 6046792 A	20000404	30	Differential interferometer system and lithographic step-and-scan apparatus provided with such a system	355/53	356/490; 356/493; 356/500; 356/509		Van Der Werf, Jan E. et al.	<input checked="" type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>
2	<input type="checkbox"/>	US 5969441 A	19991019	20	Two-dimensionally balanced positioning device with two object holders, and lithographic device provided with such a positioning device	310/12	248/178.1; 74/480R		Loopstra, Erik R. et al.	<input checked="" type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>
3	<input type="checkbox"/>	US 20020081758 A1	20020627	44	Method of manufacturing semiconductor integrated circuit device	438/16	257/E21.525		Iriki, Nobuyuki	<input checked="" type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>
4	<input type="checkbox"/>	US 5523193 A	19960604	7	Method and apparatus for patterning and imaging member	430/311	346/107.1; 347/134; 358/300; 430/20		Nelson, William E.	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>
5	<input type="checkbox"/>	US 5296891 A	19940322	9	Illumination device	355/67	347/258; 355/53		Vogt, Holger et al.	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>
6	<input type="checkbox"/>	US 5229872 A	19930720	6	Exposure device including an electrically aligned electronic mask for micropatterning	349/2	349/116; 349/25; 355/20; 430/22		Mumola, Peter B.	<input checked="" type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>	<input type="checkbox"/>